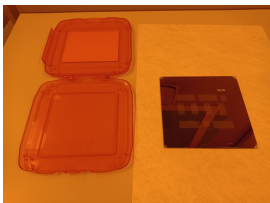
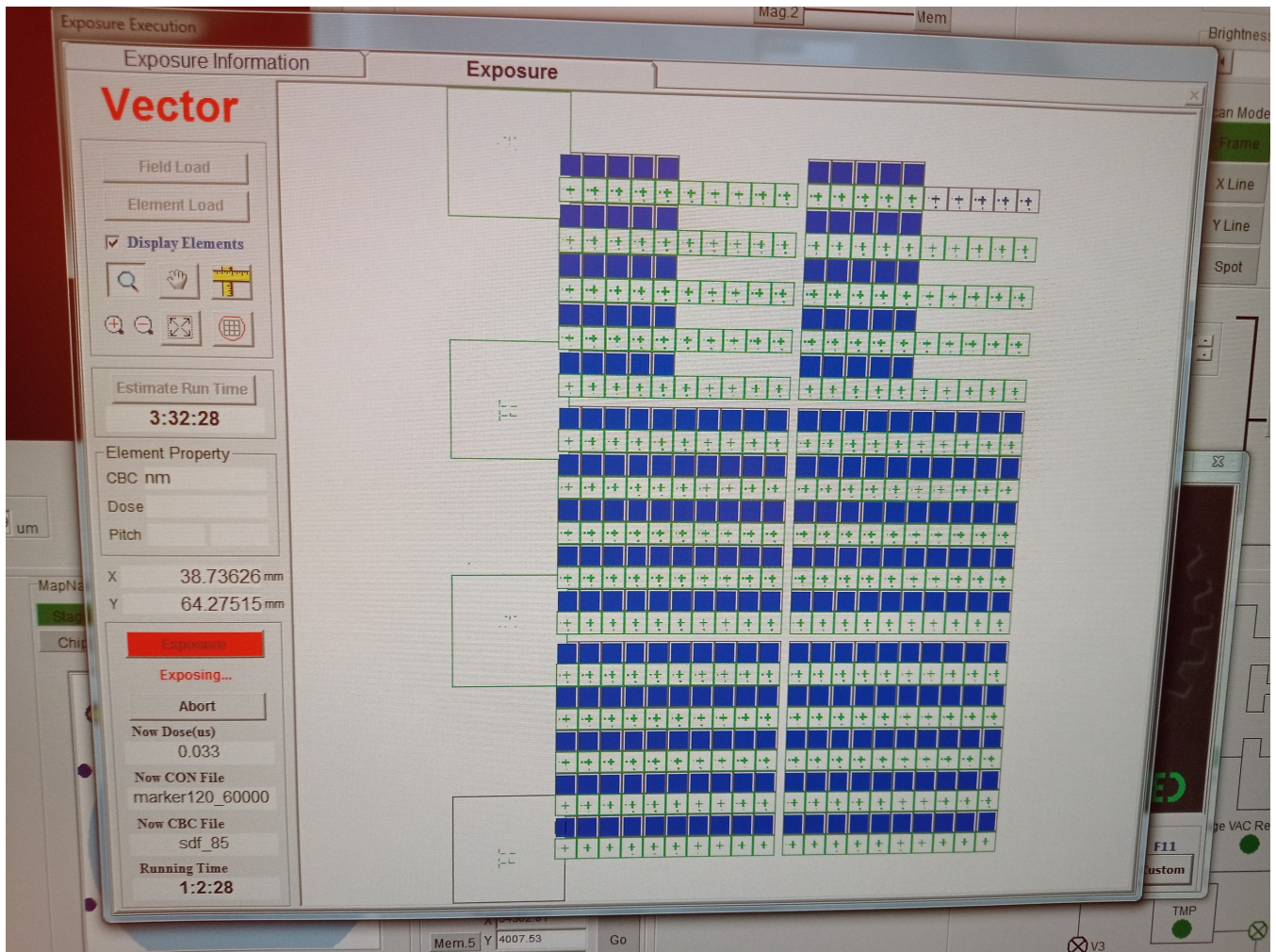


Lithographic Mask Design Service

ISOM Science and Technology Service within the framework of the field of processing techniques research



Contact information

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Technological Offers type

Technological scientific services

Research and innovation areas

- Digital Technologies, Artificial Intelligence, Cybersecurity, 5G, Robotics
- Industry, Materials and Circular Economy
- Science For Engineering and Architecture

ODS



Available from: 2015

Where?

ISOM Semiconductor Devices Group University Optoelectronics and Microtechnology Systems Institute

Keywords: | [lithographic mask](#) | [lithography](#) | [pattern design](#) | [processing techniques](#)

Lithographic mask design

CAD system for designing any kind of mask for optical lithography. The design is transferred onto a copper-coated glass slide using electron beam lithography.

Description of the services offered

- Production of all types of optical lithography masks using designs selected by the client.
 - Training in CAD design of masks for optical lithography equipment.
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Needs requested and applications

This prototyping system makes it possible to produce a high resolution optical lithography mask, in line with the client's needs, in just a few hours.

Sector or area of application

Electronics, nanotechnology, optics and optoelectronics

Differential skills

The electron beam lithography equipment at the ISOM makes it possible to make designs of just a few nanometres which are subsequently transferred to optical lithography masks. The resolution obtained using this production method is far higher than laser lithography systems.

Previous references for provision of services

Where it is

ISOM. HTSE for Telecommunications

Request for service

[Protocolo de Acceso](#)
